

Supplemental Information

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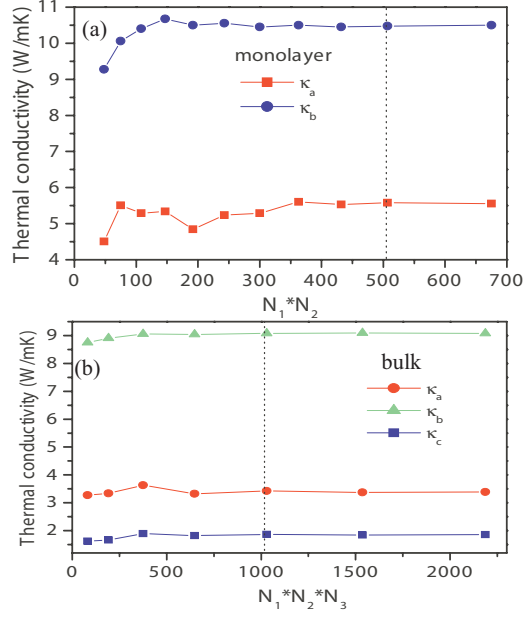


Figure S1: (Color online) Convergence tests for the thermal conductivities of both monolayer (a) and bulk (b) GaTe with increasing q-points in the phonon Brillouin zones. When increasing the q-points, we fixed $N_2/N_1 = 3$ and $N_3/N_1(N_2) = 3$ for the monolayer and bulk respectively. To accelerate the convergence, $\sigma = 1.0$ is employed in the calculations.

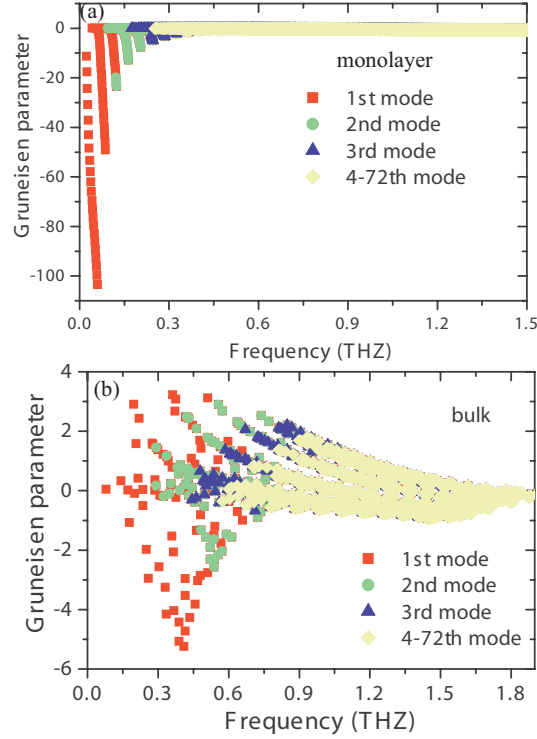


Figure S2: (Color online) Gruneisen parameter with respect to frequency for monolayer (a) and bulk (b) GaTe respectively. q -mesh of 50×150 and $15 \times 15 \times 45$ was used for monolayer and bulk GaTe respectively.

Table S1: Thermal conductivities (in unit of W/mK) and carrier mobilities (in unit of $\text{cm}^2\text{V}^{-1}\text{s}^{-1}$) at 300 K for typical two-dimensional materials. The superscripts h and e denote the hole and electron carriers respectively.

Composition	κ_a	κ_b	μ_a	μ_b
SnSe ¹	2.6	2.4	965.2 ^e	1035.8 ^e
BP ^{2,3}	10-20	20-40	2600-6400 ^h	1300-4600 ^h
Pd ₂ Se ₃ ^{4,5}	1.5	2.9	101.9 ^e	140.4 ^e
WTe ₂ ^{6,7,8}	9	20	1500-5000 ^e	
PdSe ₂ ⁹	3.7	7.2	159.9 ^e	211.6 ^e
GeS ¹⁰	7.8	10.5	529.6 ^h	1045.4 ^h
ReS ₂ ^{11,12}	50	70	338.8 ^e	799.6 ^e
GaTe ¹³	5.5	10.4	21.3 ^h	6.2 ^h

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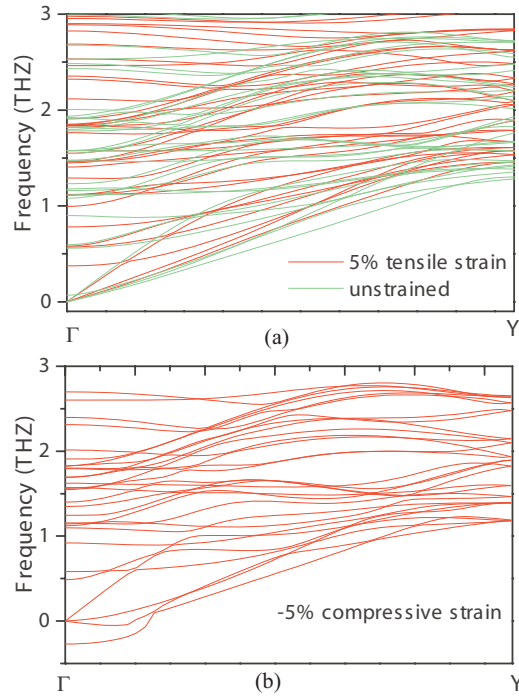


Figure S3: (Color online) Phonon dispersion along Γ -Y for the monolayer applied with $\pm 5\%$ biaxial strain. Note that the compressive strain leads to the negative phonon frequency, indicating the monolayer unstable.

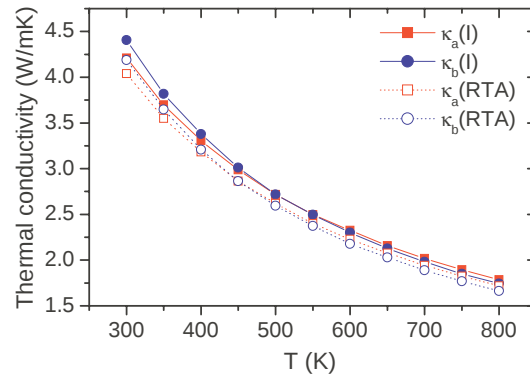


Figure S4: (Color online) Thermal conductivity versus temperature for monolayer GaTe with 5% biaxial tensile strain.

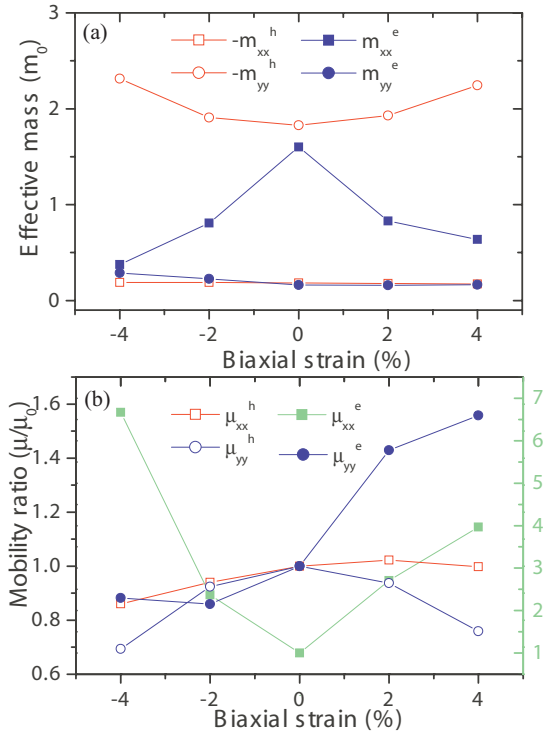


Figure S5: (Color online) Variations of effective mass (a) and charge mobilities (b) for monolayer GaTe when biaxial strain is applied to the layer.